

Notice of References Cited		Application/Control No.	Applicant(s)/Patent Under Reexamination 09/838,513 CHEN ET AL.	
		Examiner	Art Unit Julio J. Maldonado 2823	Page 1 of 1

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*		Document Number Country Code-Number-Kind Code	Date MM-YYYY	Name	Classification
*	A	US-5,937,325	08-1999	Ishida, Emi	438/655
*	B	US-6,514,859 B1	02-2003	Erhardt et al.	438/664
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	M	US-			

FOREIGN PATENT DOCUMENTS

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NON-PATENT DOCUMENTS

*		Include as applicable: Author, Title Date, Publisher, Edition or Volume, Pertinent Pages)
*	U	Mouroux, Aliette; The Reactive Formation of TiSi ₂ in the Presence of Refractory Metals (from V to W), Royal Institute of Technology, Department of Electronics, Stockholm 1,999.
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*A copy of this reference is not being furnished with this Office action. (See MPEP § 707.05(a).)
Dates in MM-YYYY format are publication dates. Classifications may be US or foreign.